

## MEASURING SYSTEM FOR PERFORMANCE OF IMAGING OPTICAL SYSTEM

### FIELD OF THE INVENTION AND RELATED ART

This invention relates to a measuring method and a measuring system for measuring the performance of an imaging optical system. More particularly, the invention concerns high precision measurement of distortion and field curvature of an imaging optical system.

Conventionally, high precision measurement of distortion and curvature of field of an imaging optical system such as an imaging lens used in a projection exposure apparatus, is based on two methods such as follows.

Figure 6 shows a first measurement method in which a plurality of patterns 1 of the same shape, formed on a reference sample 2 at positions corresponding to the view angle of a lens 5 to be inspected, are projected by the lens 5 onto a photosensitive member as reference patterns. The photosensitive member having the patterns transferred thereto is then subjected to a development process, whereby images of the reference patterns are made visible upon the photosensitive member.

The transferred and developed images of the reference patterns on the photosensitive member are then subjected to a measurement process for measuring absolute position coordinates ( $X_i, Y_i$ ) ("i" is the pattern number). The absolute position coordinates measurement is based on observation using a microscope, for example. From the measured position coordinates ( $X_i, Y_i$ ) of each patterns thus obtained and the idealistic position

coordinates ( $X_{0i}$ ,  $Y_{0i}$ ) of these patterns, the imaging position errors ( $D_{xi}$ ,  $D_{yi}$ ), that is, distortion, can be calculated in accordance with the following equations:

$$D_{xi} = X_i - X_{0i} \text{ and } D_{yi} = Y_i - Y_{0i}$$

5 In the measurement of curvature of field, after the reference patterns mentioned above are once transferred, the photosensitive member 3 is moved in X and Y directions (directions orthogonal to the optical axis of the lens to be inspected), by moving a three-axis stage 4 shown in Figure 6. The movement amount in the X and Y 10 directions is made larger than the size of each reference pattern image but smaller than the spacing of two adjacent reference pattern images. Subsequently, while keeping the coordinates (X, Y) of the stage, the stage is moved in a Z-axis direction (optical axis direction), by which the photosensitive member 3 is moved out of focus with the image plane of the lens. Then, plural reference 15 patterns are transferred to the photosensitive member.

The sequential procedure of X, Y and Z stage motions and pattern transfer operation described above is repeated until a necessary defocus amount is accomplished. After the printing 20 operation under the last defocus-condition is completed, like the distortion measurement described hereinbefore, the photosensitive member 3 is developed, whereby transferred images of the reference patterns are produced.

In this manner, in the measurement of curvature of field, 25 in relation to each view angle position, images of reference patterns are transferred to a single photosensitive member, under different defocus conditions. With respect to each view angle

position, by comparing transferred defocus images, a sharpest image is chosen and the corresponding defocus position is determined as the image plane position. The comparison of the reference pattern images is based on observation using a microscope, 5 for example. Then, the image plane positions determined at each view angle positions are compared with each other, by which the curvature of field inside the view angle of the lens 5 to be inspected can be obtained.

Figure 7 shows a second measuring method which uses an 10 interferometer in place of transferred images.

The structure of Figure 7 is what can be called a Fizeau type interferometer, and it comprises a transmission sphere lens (TS lens) 10 whose final surface is used as a reference surface, and a reflectance sphere mirror (RS mirror) 9, and so on.

Parallel light emitted from a major assembly of the 15 interferometer is reflected by a fixed mirror, mounted on a base table, in a direction of the depth of the sheet of the drawing (i.e., forwardly in the drawing). The reflected light is then reflected by a mirror which is disposed on a TS lens driving Y stage 14 and, 20 thereafter, it is reflected by another mirror 11 mounted on a TS lens driving X stage 13. The light is then incident on the TS lens 10 which is mounted on a TS lens driving Z stage 12. The light passing through the TS lens 10 is converged upon a rear focal plane of the TS lens 10, wherein the point of convergence is defined to 25 be registered approximately with the image plane of the lens 5 to be inspected. After this, the light passing through the lens 5 is collected again on the object plane.

Here, the RS mirror 9 is disposed so that the curvature center thereof coincides approximately with the point of convergence of the light upon the object plane of the lens 5. The light incident on the RS mirror 9 goes backwardly along its oncoming path, and  
5 it enters the interferometer major assembly 6 as a detection wave. On the other hand, a portion of the light incident on the TS lens  
10 is reflected by the reference surface of the TS lens 10, and it goes backwardly along its oncoming path, such that it enters  
the interferometer major assembly 16 as a reference wave.

10 Based on the detection wave and the reference wave thus entered, an interference fringe is produced in the interferometer major assembly 16. Precise measurement based on a fringe scan method, for example, is performed to measure the interference fringe, and calculation of the transmission wavefront at the  
15 measurement image point of the lens 5 is executed.

Distance measuring units 18 - 23 measure the position coordinates (TSXi, TSYi, TSZi) of the TS lens 10 adjacent its rear focal point, in the transmission wavefront measurement, as well as the position coordinates (RSXi, RSYi, RSZi) of the RS mirror  
20 9 adjacent its curvature center. The measurement may use a distance measuring gauge or an encoder, for example.

Distortion can be calculated on the basis of a tilt component of the wavefront to be measured, as well as the coordinates of the TS lens focus and the RS mirror curvature center. The error  
25 quantity (DXi, DYi) between the idealistic imaging position and the actual imaging position with respect to the X and Y directions, namely, distortion, is given by the following equations:

$$\Delta X_i = TSXi - \beta RSXi + \Delta TSXi$$

$$\Delta Y_i = TSYi - \beta RSYi + \Delta TSYi$$

where  $TSXi$  and  $TSYi$  are measured values of  $X$  and  $Y$  coordinates of the TS lens rear focal point at the  $i$ -th measurement position,  $RSXi$

5 and  $RSYi$  are measured values of  $X$  and  $Y$  coordinates of the RS mirror curvature center at the  $i$ -th measurement position, and  $\Delta TSXi$  and  $\Delta TSYi$  are correction amounts for the position coordinates of the TS lens 10 as obtainable from the tilt components in  $X$  and  $Y$  directions of the measured wavefront, which can be given by the

10 following equations:

$$\Delta TSXi = -TiltXi \lambda / NA/2$$

$$\Delta TSYi = -TiltYi \lambda / NA/2$$

where  $TiltXi$  and  $TiltYi$  are tilt components in  $X$  and  $Y$  directions obtainable from the measured wavefront,  $\lambda$  is the wavelength,  $NA$  15 is the image-plane side numerical aperture of the lens 5 to be inspected, and  $\beta$  is an idealistic magnification. Also, the symbol "i" denotes the number which represents the position of the measurement point.

Similarly, the image plane position  $DZ(x, y)$  of the 20 measurement point  $i$  having a coordinates  $(x, y)$  is determined by the defocus component of the measured wavefront as well as the  $Z$  coordinates of the TS lens focal point and the RS mirror curvature center, and it can be given by the following equation:

$$DZ(x, y) =$$

$$25 \quad TSZ(x, y) - TSZ(0, 0) + \beta \{ (RSZ(x, z) - RSZ(0, 0)) + \\ DZ_0(x, y) - DZ_0(0, 0) \}$$

wherein  $DZ_0(0, 0)$  is the defocus component obtained from the

transmission wavefront at an origin (0, 0) which is the image point  
on the optical axis,  $TSZ(x, y)$  and  $RSZ(x, y)$  are measured values  
of Z coordinates of the TS lens focal point and RS mirror curvature  
center at the point (x, y), respectively, and  $TSZ(0, 0)$  and  $RSZ(0,$   
5  $0)$  are measured values of Z coordinates of the TS lens focal point  
and RS mirror curvature center at the origin (0, 0), respectively.

The measurement at the first measurement point is completed  
with the above-described procedure, and subsequently, the TS lens  
10 and the RS mirror 9 are moved toward a next measurement position,  
if any, and a similar measurement process is performed. This  
procedure is repeated for all the measurement points.

Although Figure 7 shows a structure which is telecentric  
on the image side, the lens 5 may be an imaging lens being  
telecentric both on the object side and the image side. Further,  
15 the measurement can be done even to an imaging lens not being  
telecentric, provided that the TS lens is disposed so that the TS  
lens chief ray and the chief ray of the lens to be inspected are  
registered with each other. This can be accomplished by tilting  
the TS lens, for example.

20 In the first measuring method described above, since it needs  
a printing process and a development process, the measurement  
precision may be deteriorated by a factor attributable to the  
process, namely, wafer flatness, for example. Even after the  
development process, it needs several processes such as a  
25 measurement process using a microscope. Additionally, the  
procedure in each process is complicated. As a result, it requires  
cumbersome works and much time to obtain a single distortion

measured value. More fundamentally, there is a possibility of accumulation of errors of measured values, being accumulated with the progress of processes. Further, in relation to the measurement of curvature of field, the curvature of field must be detected on 5 the basis of the results of printing performed under different defocus conditions. This requires much time, and it involves deterioration of the measurement precision.

In the second measuring method using an interferometer, on the other hand, measurement of distortion at a measurement image point as well as measurement of the focal plane are repeated with respect to different points, and a distortion distribution and the curvature of field are calculated from the measurement results. This requires a long time for completion of the measurements to the whole view angle of the lens to be inspected. The TS lens or 10 RS mirror mounted stage may be influenced by a change in environment or the like, and a drift may be produced in the measured value of the distortion or focal plane at each measurement image points. Further, due to the increasing precision of the lens to be inspected, measurement of temperature or pressure, for example, necessary for 15 the environment correction becomes difficult.

SUMMARY OF THE INVENTION

It is accordingly an object of the present invention to enable high precision measurement of distortion and curvature of 25 field of an imaging optical system such as a lens, for example, which is free from at least one of the inconveniences described hereinbefore.

These and other objects, features and advantages of the present invention will become more apparent upon a consideration of the following description of the preferred embodiments of the present invention taken in conjunction with the accompanying drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Figure 1 is a schematic view of a first embodiment of the present invention.

10 Figure 2 is a schematic view of an interference measuring unit in a second embodiment of the present invention.

Figure 3 is a schematic view of a third embodiment of the present invention.

15 Figure 4 is a schematic view of a fourth embodiment of the present invention.

Figure 5 is a schematic view of a fifth embodiment of the present invention.

Figure 6 is a schematic view for explaining a first conventional measuring method.

20 Figure 7 is a schematic view for explaining a second conventional measuring method.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

Figure 1 shows a first embodiment of the present invention.

25 In Figure 1, the interferometer comprises a major assembly 16 and two sets of RS mirrors 9 and 25 and TS lenses 10 and 24 to be used for an image point on an optical axis (which is a standard

image point for providing a reference value for drift correction) and for another measurement point, respectively. The structure of Figure 1 is what is called a Fizeau type interferometer, and the final surface of the TS lens (Transmission Sphere lens) is used 5 as a reference surface. It is to be noted here that, while the standard image point can be set at any desired position if predetermined, from the standpoint of balance to all the measurement points, preferably an image point on the optical axis may be chosen therefor.

10       Hereinafter, the TS lens 24 and the RS mirror 25 for the image point on the optical axis will be referred to as a drift value referring TS lens 24 and a drift value referring RS mirror, respectively. The TS lens 10 and the RS mirror 9 for the other measurement point will be referred to simply as a TS lens 10 and 15 an RS mirror 9.

Parallel light emitted from the major assembly 16 of the interferometer is reflected by a fixed mirror, mounted on a base table 15, in a direction of the depth of the sheet of the drawing (i.e., forwardly in the drawing). The reflected light is then 20 reflected by a mirror which is disposed on a TS lens driving Y stage 14 and another mirror which is mounted on a TS lens driving X stage 13. The reflected light is then incident on the TS lens 10 which is mounted on a TS lens driving Z stage 12. The light passing through the TS lens 10 is converged at a position which is upon 25 the rear focal plane of the TS lens 10 and which is substantially coincident with the object plane of the lens 5. The thus converged light passes the lens 5 to be inspected and, thereafter, it is

collected again upon the image plane of the lens 5. At the image plane side, the RS mirror (Reflectance Sphere mirror) 9 is disposed so that the curvature center thereof coincides approximately with the point of convergence of the light upon the image plane of the lens 5. Thus, the light as reflected by the RS mirror 9 goes backwardly along its oncoming path, and it enters the interferometer major assembly 16 as a detection wave.

On the other hand, a portion of the light incident on the TS lens 10 is reflected by the reference surface of the TS lens 10, and it goes backwardly along its oncoming path, such that it enters the interferometer major assembly 16 as a reference wave.

The drift value referring interferometer has a similar structure. Light passing through the drift value referring TS lens 24 is converged at a rear focal plane of the lens 24. The position 15 of the convergence point approximately coincides with the object plane of the lens 5 to be examined. The collected light passes the lens 5 and, thereafter, it is collected again at the image plane side. At the image plane side, the drift value referring RS mirror 25 is disposed so that its curvature center approximately coincides 20 with the light convergence point upon the image plane of the lens to be examined. The light reflected by the RS mirror goes backwardly along its oncoming path, and it enters the interferometer major assembly 16 as a drift value referring detection wave.

25 On the other hand, a portion of the light entering the drift value referring TS lens 24, fixedly mounted on the base table 15, is reflected by the reference surface of the lens 24, and it goes

backwardly along its oncoming path and enters the interferometer major assembly as a drift value referring reference wave.

In this embodiment, the drift value referring RS mirror 25 and the other RS mirror 9 for the remaining measurement point have different curvature radii and, also, the distance between the final surface of the drift value referring TS lens 25 and the rear focal point thereof differs from the distance between the final surface of the TS lens 10 for the remaining measurement point and the rear focal point thereof. However, these sizes may be made equal to each other. Further, the TS lens 24 and the RS mirror 25 may not be fixed but they may be provided on a movable stage.

In this embodiment, as regards the standard image point, the measurement is performed only by use of the drift value referring optical system.

The TS lens driving stages 12, 68 and 69 as well as the RS mirror driving stages 8, 70 and 71 should be structured so as to avoid disturbance to the light which passes the drift value referring optical system. In this embodiment, as shown in Figure 2, the TS lens is provided as an  $r\theta z$  stage about the optical axis of the drift value referring optical system, and there are a central portion of a  $\theta$  stage 69 and an opening. This facilitates the mechanical design for avoiding the disturbance or interference.

The RS mirror 9 and the drift value referring RS mirror 25 can be scanningly moved in the optical axis direction by means of a piezoelectric device, for example. At each scan positions, an interference fringe due to the drift value referring reference wave and the drift value referring detection wave (hereinafter, first

interference fringe), as well as an interference fringe due to the reference wave and the detection wave (hereinafter, second interference fringe) are measured by a camera inside the interferometer major assembly, as the intensity data. The measurement result is transmitted to a host computer, and transmission wavefronts (hereinafter, first transmission wavefront and second transmission wavefront) are calculated as phase data of the first and second interference fringes. The interference fringe measurement uses a fringe scan method, such that high precision phase measurement is enabled. The camera inside the interferometer major assembly, for detecting the interference fringe intensity may be provided in two independent channels for the first and second interference fringes, separately, or it may be provided in a single channel structure wherein both of the first and second interference fringes are detected by a one and the same camera.

The distance measuring units 18 - 23 and 26 - 31 are operable to measure the position coordinates (TSXi, TSYi, TSZi) adjacent the rear focal point of the TS lens 10 in the transmission wavefront measurement, the position coordinates (RSXi, RSYi, RSZi) adjacent the curvature center of the RS mirror 9, the position coordinates (TSX0i, TSY0i, TSZ0i) adjacent the rear focal point of the drift value referring TS lens 24, and the position coordinates (RSX0i, RSY0i, RSZ0i) adjacent the curvature center of the drift value referring RS mirror 25.

In the position coordinates measurement, a mirror is disposed at a position close to both points, and this mirror

position is measured by using an interference distance gauge, for example. Where the measurement is carried out by using a mirror placed away from the both points, the posture of the TS lens and RS mirror (i.e., pitching, yawing and rolling) may be measured so 5 that the distance between the measurement point and the idealistic measurement point can be corrected.

In this embodiment, the measuring units 18 - 23 use 10 interference distance gauges, and the drift value referring optical system and the optical system for the other measurement point are measured separately. From the difference in measured 15 distance in this structure, the optical system for the measurement point can always be represented by a relative value with respect to the drift value referring optical system, such that the influence of the drift of the movable stage in the optical system for the measurement point can be reduced. Thus, the measurement with the drift value referring optical system for measuring the reference image point is performed frequently, in other words, it is done many times more than the measurement for the measurement point.

Next, measurement of distortion and curvature of field in 20 the present invention will be described in greater detail.

The drift value referring TS lens 24 and RS mirror 25 are fixed at an image point on the optical axis and an object point on the optical axis, that is, a standard point. In this state, the RS mirror 9 and the RS lens 10 are moved toward the i-th 25 measurement point. The motion is performed while aiming at the coordinates in which a conjugate relation is substantially satisfied between the rear focal point of the TS lens and the

curvature center of the RS mirror. The coordinates being aimed at are set as relative coordinates with respect to the RS mirror 25 and TS lens 24, being disposed at the origin.

Subsequently, measurement of the transmission wavefront is 5 performed at the i-th measurement point. Simultaneously, the position coordinates of the TS lens rear focal point, RS mirror curvature center, the drift value referring TS lens rear focal point, and the drift value referring RS mirror curvature center. Here, the transmission wavefront which is obtainable from a standard 10 point for referring to the drift value is called a first transmission wavefront, and the transmission wavefront which is obtainable from the i-th measurement point is called a second transmission wavefront.

Then, the tilt component and the defocus component of the 15 measured transmission wavefronts are calculated. These components can be detected by fitting the transmission wavefront data in accordance with Zernike polynomial, using a least square method, for example. The calculation is done with respect to each of the first and second transmission wavefronts.

From the tilt components of the measured first and second 20 transmission wavefronts, the measured coordinates ( $TSX_i$ ,  $TSY_i$ ) of the TS lens 10, the measured coordinates ( $RSX_i$ ,  $RSY_i$ ) of the RS mirror 9, the measured coordinates ( $TSX_{0i}$ ,  $TSY_{0i}$ ) of the drift value referring TS lens 24, and the measured coordinates ( $RSX_{0i}$ ,  $RSY_{0i}$ ) 25 of the drift value referring RS mirror 25, and in accordance with equations below, error quantities ( $DX_i$ ,  $DY_i$ ) between the idealistic imaging position and the actual imaging position with

respect to the X and Y directions, namely, the distortion, can be calculated.

$$\Delta X_i = \{TSXi - (TSX0i - TSX01)\} - \beta \{RSXi - (RSX0i - RSX01)\} + \Delta TSXi$$

$$\Delta Y_i = \{TSYi - (TSY0i - TSY01)\} - \beta \{RSYi - (RSY0i - RSY01)\} + \Delta TSYi$$

5 where  $TSX01$  and  $TSY01$  as well as  $RSX01$  and  $RSY01$  are measured coordinates of the drift value referring TS lens and RS mirror in the first measurement,  $\Delta TSXi$  and  $\Delta TSYi$  are correction amounts for the position coordinates of the TS lens as obtainable from the tilt components in X and Y directions of the measured wavefront, which  
10 are given by the following equations:

$$\Delta TSXi = -(TiltXi - (TiltX0i - TiltX01)) \lambda / NA / 2$$

$$\Delta TSYi = -(TiltYi - (TiltY0i - TiltY01)) \lambda / NA / 2$$

wherein  $TiltX0i$ ,  $TiltY0i$ ,  $TiltXi$  and  $TiltYi$  are tilt components in X and Y directions at the standard image point and the measurement 15 image point as obtainable from the first and second wavefronts in the i-th measurement,  $TiltX01$  and  $TiltY01$  are tilt components in X and Y directions of the reference image point (the position of the drift value referring TS lens 24 and RS mirror 25) in the first measurement,  $\lambda$  is the wavelength,  $NA$  is the image-plane side 20 numerical aperture of the lens 5 to be inspected,  $\beta$  is an idealistic magnification, and  $i$  is the number which represents the position of the measurement point.

The image plane position  $DZ(Xi, Yi)$  of the i-th measurement point can be expressed by the following equation, in terms of the 25 defocus components of the first and second transmission wavefronts, and the coordinates of the TS lens focal point and the curvature center of the RS mirror, as follows.

$$DZ(Xi, Yi) = TSZ(Xi, Yi) - TSZ(X0i, Y0i) + \beta \{ RSZ(Xi, Yi) - RSZ(X0i, Y0i) \} + DZ0(Xi, Yi) - DZ0(X0i, Y0i)$$

wherein  $DZ0(X0i, Y0i)$  and  $DZ0(Xi, Yi)$  are defocus components  
5 obtainable from the first and second transmission wavefronts,  
TSZ( $X_i, Y_i$ ) and RSZ( $X_i, Y_i$ ) are measured values of the TS lens focal  
point and RS mirror curvature center, TSZ( $X_0i$ ) and RSZ( $X_0i, Y_0i$ )  
are measured values of the position coordinates of the drift value  
referring TS lens rear focal point and the drift value referring  
10 RS mirror curvature center. The defocus component from the  
measurement wave can be calculated by computing the contrast value  
while applying a spherical component, corresponding to the defocus  
component, to the measurement wavefront. The defocus position  
with a best contrast value are taken as the image point at the point  
15 ( $X_i, Y_i$ ), for example.

The measurement with regard to the  $i$ -th measurement point  
is completed as above. If there is a subsequent measurement point,  
the TS lens 10 and the RS mirror 9 are moved toward the next  
measurement position, and the procedure from the measurement of  
20 the transmission wavefront is repeated again.

After the measurement at the last measurement point is  
completed, the error quantity ( $\Delta X_i, \Delta Y_i$ ) between the idealistic  
imaging point and the actual imaging point at each measurement  
points and the focal plane  $DZ(Xi, Yi)$  are synthesized, such that  
25 a distortion distribution and curvature of field within the view  
angle of the lens to be examined are obtained while even taking  
into account the transmission wavefront.

In this embodiment, an interference distance gauge is used to suppress the drift of a movable stage, and the effect of drift due to any other factor is corrected by continuously monitoring the axial wavefront. Thus, high precision measurement of 5 distortion and curvature of field is enabled.

A second embodiment of the present invention is arranged so that any change with respect to time of distortion and curvature of field can be observed without an observation system for a reference image point as used in the first embodiment, and the 10 structure is similar to the second measuring method.

In order to determine the curvature of field and the distortion distribution inside the view angle of a lens to be inspected, it is necessary to measure the distortion and focal plane at different image points within the view angle. In this 15 embodiment, during measurement with respect to the different image points, measurement of an axial image point corresponding to a standard image point is performed many times. From the quantity of changes in distortion and focal plane at the standard image point, a variation component with respect to time at the other measurement 20 points is calculated, and correction is performed accordingly.

If it is assumed that, with regard to the i-th measurement point  $(x_i, y_i)$ , the measurement of a standard point just before it is performed in relation to the  $(i-a)$ th measurement point and the measurement of a standard point just after it is performed at 25 the  $(i+b)$ th measurement point, distortion after correction of the i-th variation quantity with respect to time can be determined by the following equations:

```
DXdc(Xi, Yi) =  
    DX(Xi, Yi)-(DX0(i+b)-DX0(i-a))a/(a+b)-  
    {DX0(i-b)-X0(1)}  
DYdc(Xi, Yi) =  
    DY(Xi, Yi)-(DY0(i+b)-DY0(i-a))a/(a+b)-  
    {DY0(i-b)-X0(1)}
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The correction formulae mentioned above are determined while taking the variation quantities with respect to time of each measurement image points as linear complement to the variation quantity with respect to time of the standard image point. Here, 10 DXdc(Xi, Yi) and DYdc(Xi, Yi) are distortion at the i-th measurement point after correction of the variation with respect to time, DX(Xi, Yi) and DY(Xi, Yi) are measured values of distortion at the i-th measurement point, and DX0 and DY0 are distortion at the standard image point. Each argument show the correspondence of the 15 measurement at the standard image point to the number of measurement point. Also, the argument "1" shows that the first measurement is to the standard image point.

As regards the detection of the focal plane, similar 20 correction is possible. More specifically:

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DZ(Xi, Yi) =  
    TSZ(Xi, Yi)-(TSZ0(i+b)-(TSZ0(i-a))a/(a+b))  
    -TSZ0(i-a)+β(RSZ(Xi, Yi)-(RSZ0(i+b))  
    -(RSZ0(i-a))a/(a+b)-RSZ0(i-a))+DZ0(Xi, Yi)  
    -(DZ0(i+b))-DZ0(i-a)a/(a+b)-DZ0(i-a)
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where DZ(Xi, Yi) is the defocus component at the i-th measurement point after correction of the variation with respect to time, TSZ(Xi,

Y<sub>i</sub>) and RSZ(X<sub>i</sub>, Y<sub>i</sub>) are measured values of coordinates of the TS lens focus and RS mirror curvature center position at the i-th measurement point, TSZ0 and RSZ0 are measured values of the TS lens focus and RS mirror curvature center position at the standard image point. Each argument shows the correspondence of the measurement at the standard point with the number of measurement point. DZ0(X<sub>i</sub>, Y<sub>i</sub>) denotes the defocus component obtained from the transmission wavefront. The argument "1" shows that the first measurement is to the standard image point, and  $\beta$  denotes the idealistic imaging magnification of the lens being examined.

In this embodiment, as regards the method of complementing the variation amount at each measurement image point with respect to time, straight complement based on the amount of changes, with time, between two standard-image-point measurements before and after the measurement image point. However, the number of standard image points to be used for the complementation may be other than two. Also, a curved complementation may be used.

Where the above-described correction is carried out to the whole measurement points, any change in distortion or curvature of field with respect to time can be corrected and reduced even by use of a single set of TS lens and RS mirror. Therefore, a lens performance measuring system capable of doing high precision measurement is accomplished.

Figure 3 shows the structure of a third embodiment according to the present invention. While the first embodiment uses two sets of TS lenses and RS mirrors, this embodiment uses plural sets of TS lenses and RS mirrors, to enable simultaneous measurement at

plural measurement points in addition to the standard image point. Because of the increase in number of TS lenses and RS mirrors, independent motion of each TS lens and RS mirror is not adopted in this embodiment.

5       The curvature centers of each spherical mirrors of the RS  
mirror group 33 are disposed to satisfy the conjugate relation with  
the rear focal points of corresponding lenses of the TS lens group  
32. Namely, where the position coordinates of the rear focal point  
of the i-th TS lens are expressed as (TSXi, TSYi) while taking the  
10 optical axis as an origin, the position (RSXi, RSYi) of the  
curvature center of the i-th RS mirror is given by the following  
equations:

$$RSXi = TSXi/\beta$$

$$RSYi = TSYi/\beta$$

15 where  $\beta$  is the idealistic imaging magnification of the lens 5 being  
inspected.

In this embodiment, the rear focus position of each TS lens  
as well as the curvature center position of each RS mirror, after  
being manufactured, are measured beforehand. As regards the  
20 measurement of the focus position of each TS lens, an RS mirror  
disposed on a movable stage may be used and, without using the lens  
to be examined, a Fizeau type interferometer may be constructed  
directly to each TS lens. From the position coordinates of the  
RS mirror and the tilt component of the measurement wavefront, the  
25 rear focus position can be measured. As regards the RS mirror  
group, similarly, a TS lens may be mounted on a movable stage, and  
the curvature center position can be measured.

The manner of calculating distortion and focal plane at each measurement points, during and after the measurement, is the same as in the first embodiment. However, since plural measurement points can be measured simultaneously in this embodiment, the influence of stage drift or any change in environment is reduced. Therefore, the measurement time can be shortened considerably.

Figure 4 shows the structure of a fourth embodiment according to the present invention. In this embodiment, the RS mirror group of the second embodiment is replaced by a plane mirror 34.

10 The plane mirror 34 is disposed upon the image plane of the lens 5 to be examined. For the measurement, the lens should be telecentric on one side or both sides. If it is telecentric on one side thereof, the chief ray of the TS lens and the chief ray of the lens to be examined should be registered with each other. 15 Thus, the TS lens may be tilted, for example, to this end.

Although the structure is simplified by replacing the RS mirror by a flat mirror, only the revolutionally symmetrical component of the transmission wavefront of the lens to be examined can be calculated with this structure. Therefore, distortion can 20 not be measured in this embodiment. However, simultaneous measurement of the focal plane with respect to different measurement points can be done without difficulties involved in the manufacture of the RS mirror group. This is an advantage in this embodiment. The calculation of the focal plane is similar 25 to that of the second measuring method described hereinbefore.

Figure 5 shows a fifth embodiment of the present invention. In this embodiment, the lens performance measuring system of the

present invention is incorporated into a projection exposure apparatus having a projection optical system which is the lens to be examined. This embodiment enables high precision measurement of distortion and curvature of field of a projection optical system 5 within the major assembly of the projection exposure apparatus.

In Figure 5, the light emitted from an exposure light source 43 such as an excimer laser is transformed by a beam shaping optical system 44 into a beam shape symmetrical with respect to the optical axis, and then it is directed to a light path interchanging mirror 10 45. The mirror 45 is retracted out of the light path during the normal exposure process, so that the light is directed toward an illumination optical system 47. More specifically, the light emitted from the beam shaping optical system 44 enters an incoherency-transforming unit 46 by which the coherency of the 15 light is reduced. After this, the light passes the illumination optical system 47, and it illuminates the surface of a reticle 56. The light passing through the reticle enters a projection optical system 5 which is the lens to be examined, and so that a pattern formed on the reticle 56 surface is projected onto the surface of 20 a wafer 57.

There is a wafer chuck 58 disposed inside the view angle of the projection optical system 5.

The structure of an interferometer as being guided by the light path interchanging mirror 45 will be described below.

25 For measurement of the lens performance, the light emitted from the beam shaping optical system 44 is reflected by the light path interchanging mirror 45 inserted into the light path, and it

passes through a directing optical system 48 and enters a condensing lens 49. Adjacent the focal point of the condensing lens 49, there is a pinhole 50. The light passing through the pinhole 50 is transformed again into parallel light by means of a collimator lens 51. The diameter of the pinhole 50 may be set to be approximately equal to the diffraction limit determined by the numerical aperture of the condensing lens 49, to regulate the transverse mode of light. The parallel light emitted from the collimator lens 51 is divided by a half mirror 52 into two. In this embodiment, the light reflected by the half mirror is directed to a drift value referring optical system, while the light passing through the mirror is directed to an optical system for the other measurement points.

In the measurement, the wafer chuck 58 moves out of the view angle of the projection optical system and, in place of it, an RS mirror 9 and a drift value referring RS mirror 25 are inserted into the view angle.

In the drift value referring optical system, the light reflected by the half mirror 52 is directed to a collimator lens 54. The rear focal point of the collimator lens 54 is disposed to be approximately registered with the reticle surface 56. As a result, the light collected by the collimator lens 54 is collected again by the projection optical system 5, at a position close to the wafer surface 57. The drift value referring RS mirror 25 is fixedly mounted on a wafer stage 59 so that the curvature center position thereof is disposed to be approximately coincident with a conjugate point of the focal point position of the collimator lens with respect to the projection optical system 5. The light

reflected by the RS mirror 25 goes backwardly along its oncoming path, and it is incident again on the half mirror 52.

The light passing through the drift value referring optical system (collimator lens 54, RS mirror 25 and the like) and impinging 5 on the half mirror 52 then passes therethrough, and the light is incident on a half mirror 60 inside the interferometer major assembly 66.

On the other hand, in the optical system for the measurement points, the light passed through the half mirror 52 is reflected 10 by a half mirror 53, and it is directed to a collimator lens 55. The collimator lens 55 is mounted on an X-Y-Z movable stage, and the light convergence point thereof is inside the view angle of the projection optical system 5. It enables motion to any object point adjacent to the reticle surface 56. The manner of directing 15 light to the collimator lens 55 may be the same as in the first embodiment. The rear focal point of the collimator lens 55 is approximately registered with the reticle surface 6 of the projection optical system 5, and the curvature center of the RS mirror 9 is disposed to be approximately coincident with a conjugate 20 point of the focal point position of the collimator lens 55 with respect to the projection optical system 5. As a consequence, the light collected by the collimator lens 55 is collected again on the wafer surface 57 by means of the projection optical system 5. The light is then reflected by the RS mirror 9 which is disposed 25 on an X-Y-Z movable stage 66, fixedly mounted on the wafer stage 59. The reflected light goes backwardly along its oncoming path, toward the half mirror 53.

The inside structure of the interferometer major assembly  
66 will now be described.

The light incident on the half mirror 60 is divided thereby  
into two. The light reflected by the half mirror 60 (hereinafter,  
5 "light A") is reflected by a flat mirror 61, and the beam diameter  
thereof is expanded by a beam expander 67. After this, the light  
passes through a half mirror 64. On the other hand, the light  
transmitted through the half mirror 60 (hereinafter, "light B")  
is reflected by a flat mirror 62 which is mounted on a movable stage  
10 63, being moved by a piezoelectric device, for example, and the  
light is projected on the half mirror 64. The light B is reflected  
by the half mirror 64, and goes substantially along the same path  
as the light A. The optical path difference between the light A  
and the light B, from being divided by the half mirror 60 to being  
15 substantially combined into the same path by the half mirror 64,  
is registered within the range of the coherence length of the  
exposure light source 43. What can be observed by a CCD camera  
65 is an interference fringe produced by the light A and the light  
B being laterally shifted with respect to the light A.

20 The observed interference fringe is a differentiated value  
to the lights A and B, in the same radial direction about the optical  
axis, having wavefront aberrations corresponding to the sum of the  
projection optical system 5 and the intermediate optical systems.  
By integrating it and subtracting therefrom the wavefront  
25 aberration and shape errors of the intermediate optical systems,  
the wavefront aberration of the projection optical system 5 can  
be determined. The wavefront calculation may be based on a fringe

scan method in which the movable stage 63 is moved by an amount corresponding to the wavelength. As regards the wavefront aberration and shape errors of the intermediate optical systems, they may be measured beforehand by using a separate interferometer  
5 or, alternatively, it may be measured by using a system error measuring method. In such system error measuring method, an RS mirror 25 may be disposed below the collimator lens 54, and the wavefront aberration is measured in three conditions of zero deg., 180 deg., and apex reflection. From the results, the wavefront  
10 aberration of the intermediate optical systems can be detected.

As regards the wavefront passing through the optical system for the measurement points (i.e., collimator lens 55, RS mirror 9 and the like), it can be measured by using a similar interferometer.

15 Simultaneously with the wavefront measurement at the standard image point, referring to the drift value, and at the remaining measurement points, the position coordinates of the rear focal points of the collimator lenses 34 and 55 and the curvature centers of the RS mirrors 9 and 25 can be measured, in a similar way as the first embodiment.

The manner of measuring distortion and curvature of field on the basis of the wavefront data and position coordinates described above, is essentially the same as in the first embodiment.

25 The measuring system for measuring the performance of an imaging optical system as has been described above enables correction of the influence of a change with respect to time, such as drift, for example, which adversely affects the measurement.

Additionally, the measurement does not need complicated and numerous processes such as exposure and development, in the lens evaluation. Moreover, it can be done without being influenced by a drift of a movable stage or an environmental variation. As a 5 result, the performance of a lens can be measured automatically, easily and precisely.

While the invention has been described with reference to the structures disclosed herein, it is not confined to the details set forth and this application is intended to cover such 10 modifications or changes as may come within the purposes of the improvements or the scope of the following claims.

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